

UHV SYSTEM PV116

Description

The PV116 system is versatile R&D tool offering the flexibility of multi-deposition techniques in a single platform. It is configured to allow fast and simple change between multi-target sputtering or multi-source evaporation with a guaranteed base pressure in the 10^{-8} mbar range.

Specification

A unique feature of these systems is that the target mounting stage on the bottom face of the chamber is designed so that it can be effortlessly exchanged with matching stages that are configured with thermal, e-beam or combination sources, providing a truly multi-technique, multi-deposition system that is ideal for both small scale production and R&D prototyping.

Supported Configurations:

- thermal evaporation boats
- magnetrons sources
- crucibles
- different combinations of above

All sources can be equipped with integrated manual or automatic shutters and the system has a wealth of target/sample viewports.

The chamber is equipped with a large, easy access vacuum door which is dual viton sealed with differential pumping in the seal interspace. This maintains an excellent base pressure whilst providing perfect internal access. The system employs efficient double wall water cooling throughout.

In standard setup the chamber is equipped for multi-sample mounting. An optional sample manipulator is available for up to 4 sample holder stages with integrated sample heating and cooling.

The chamber has dedicated spare ports for;

- ion source for cleaning
- thickness monitor,
- Residual Gas Analyser
- load lock chamber with transfer
- gas dosing

The system is delivered with all necessary power supplies and control units in a standalone 19" cabinet.

